

AMENDMENTS

IN THE SPECIFICATION:

1. Please replace the paragraph beginning on Page 12, Line 16 with the following re-written paragraph:

B1
FIGURE 4 illustrates a graph of one embodiment of pellicle transmission maxima for various exposure wavelengths. Conventional pellicles are designed to have transmission maxima at the selected exposure wavelengths of an associated photolithography system. As shown in FIGURE 4, the transmission peaks for the pellicle tested occur at exposure wavelengths of 248 nanometers (nm) (e.g., deep UV), 365 nm (e.g., I-line), and 436 nm (e.g., G-line). The placement of the transmission peaks versus exposure wavelength is directly related to the physical thickness of film 51. In conventional pellicles, the optical thickness of the thin film is designed to be an even multiple of the exposure wavelengths used in the photolithography system in order to produce a peak in transmission at or near one or more of the exposure wavelengths.

IN THE CLAIMS:

For the convenience of the Examiner, all pending claims of the present application are shown below in clean form whether or not an amendment has been made. Please refer to the attached sheet showing a mark-up version of the amendments to the claims.

Claims 1 – 6 previously cancelled without prejudice or disclaimer.

B1
B2
7. (Twice Amended) A pellicle comprising:
a frame; and
a thin film including an optical thickness coupled to the frame, the optical thickness operable to produce a peak in transmission for normal incidence light at a wavelength greater than an exposure wavelength and maximize transmission of the exposure wavelength at an angle of incidence greater than zero.